

INVESTIGATION OF JUNCTION PROPERTIES OF CdS/CdTe SOLAR CELLS AND THEIR CORRELATION TO DEVICE PROPERTIES

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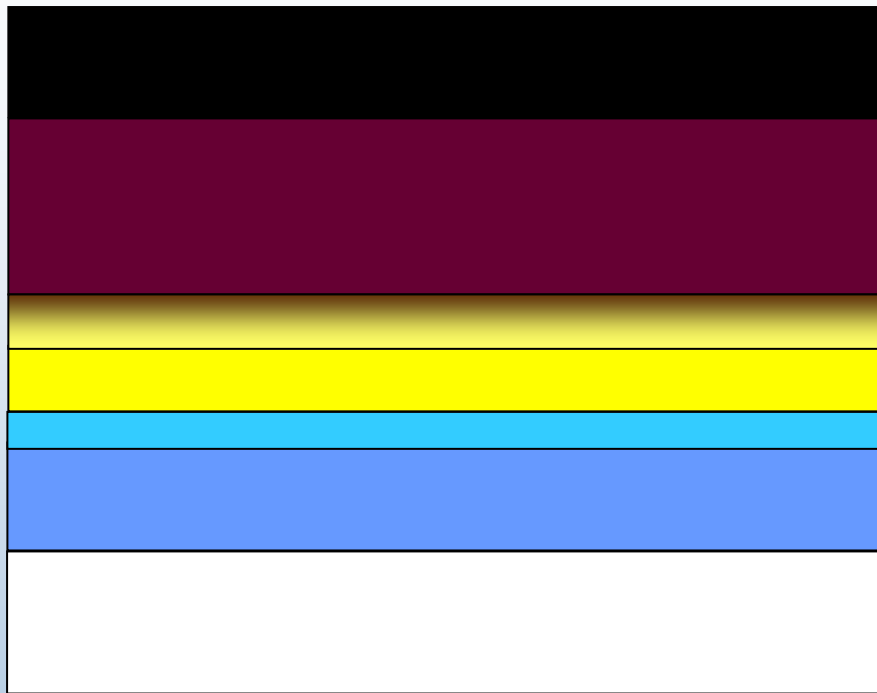
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Objective - Junction Studies

- Understand the nature of the junction in the CdTe/CdS device
- Correlate the device fabrication parameters to the junction formation
- Develop a self consistent device model to explain the device properties

Detailed analysis of CdS/CdTe and SnO₂/CdTe devices prepared using CSS CdTe.



Contact - doped graphite,
Cu/Au

CdTe

CdS/CdTe Interface

CdS- CBD

Buffer layer

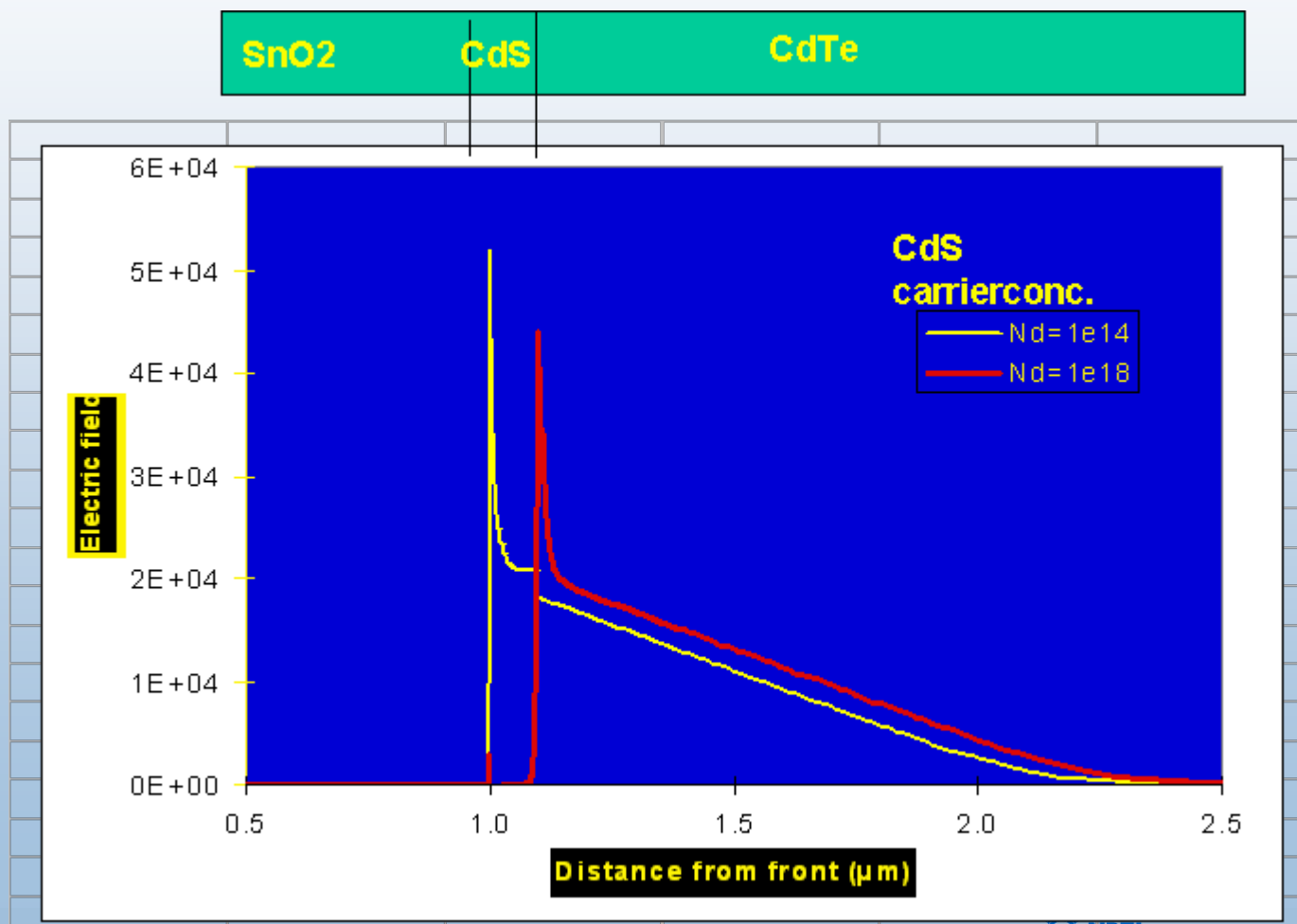
SnO₂

Glass

CdTe Device Structure

n⁺-p device model for CdS/CdTe device (6/95)- based on blue QE loss:

- One sided junction with depletion width entirely in CdTe.
- Only field assisted collection.



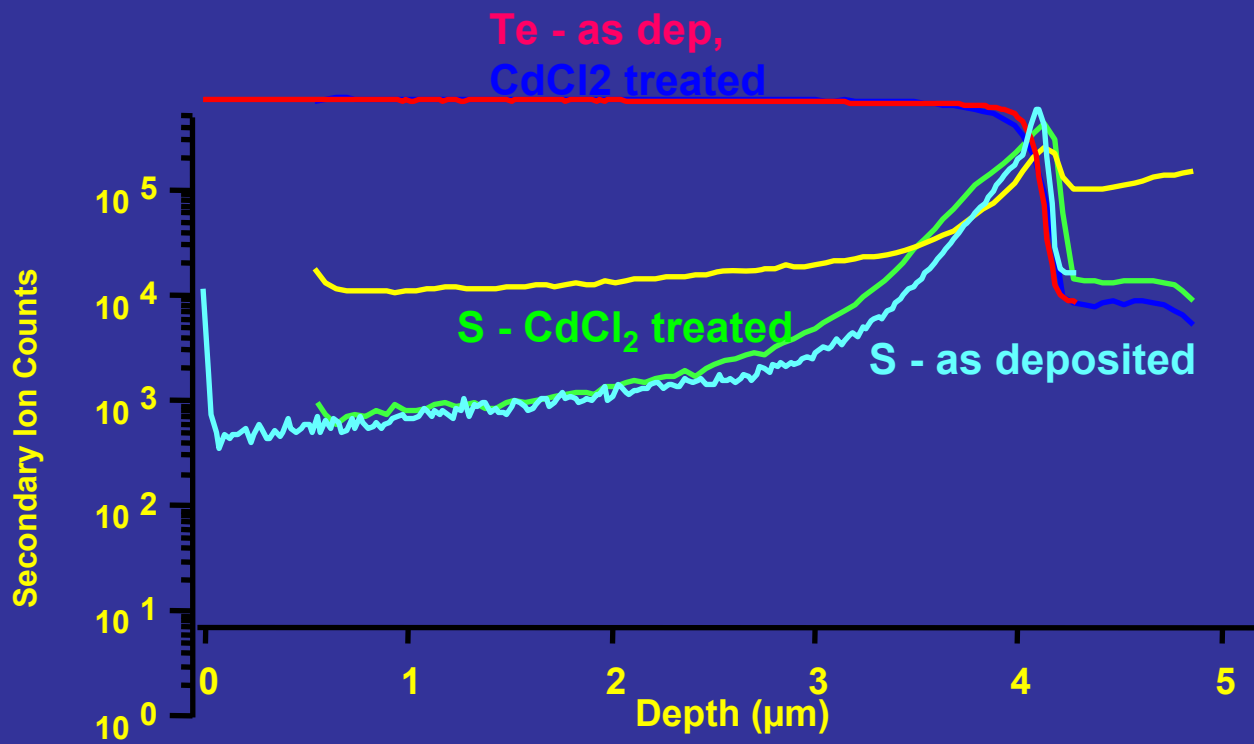
Problems with the n⁺-p model

- **Phenomenological Model – can explain the device performance but without physical basis.**
- **CBD CdS has carrier concentration around $10^{13}/\text{cm}^3$ which is even less than CdTe**

Here we present our interface/junction analysis using Secondary Ion Mass Spectrometry (SIMS), Modulated reflectance techniques and Electron Beam Induced Current (EBIC) to elucidate the junction properties.

SIMS Results

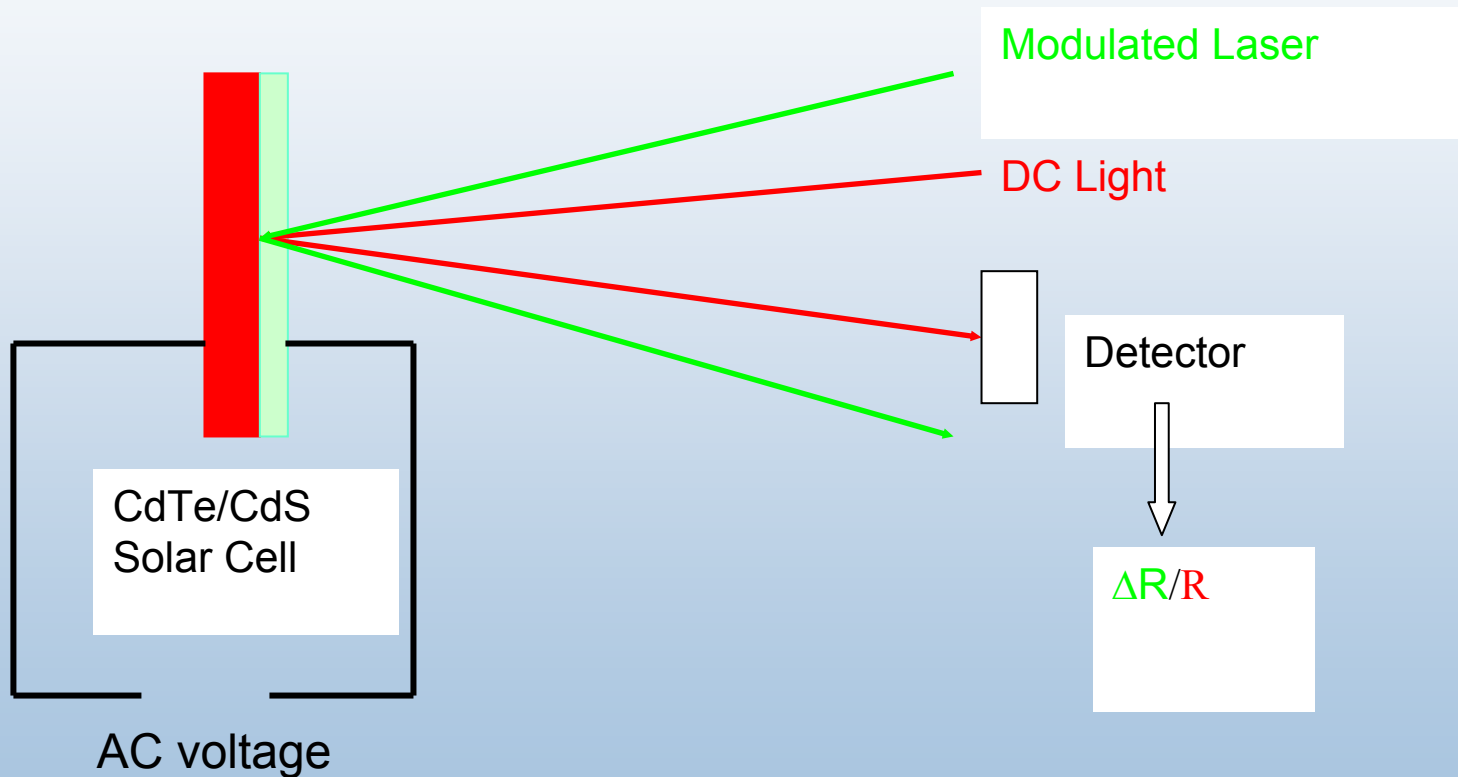
- Roughness of the samples (RMS – 0.5 μm) makes it impossible to resolve the features at CdS/CdTe interface.
- NREL SIMS and Microscopy groups developed sample preparation with polishing to improve the interface resolution.



Observations

- Interdiffusion at CdS/CdTe interface increases with T_{sub} and CdCl₂ HT
- Accumulation of Cl at CdS/CdTe interface after CdCl₂ HT. Level of Cl increases with level of HT
- Cl is a n-type dopant in both CdS and CdTe; also in the intermixed alloy

Photo- or Electro-Modulated Reflectance (PR or ER)



Reflectance modulation

$$R = \left| \frac{n - n_a}{n + n_a} \right|^2$$

$$n^2 = \varepsilon_1 + i \varepsilon_2, \quad n_a^2 = \varepsilon_a \text{ (real)}$$

Near band-gap \Rightarrow major contribution is from $\Delta\varepsilon_1$:

$$\frac{\Delta R}{R} \approx \alpha \Delta \varepsilon_1$$

Fitting Modulation Reflectance Spectrum

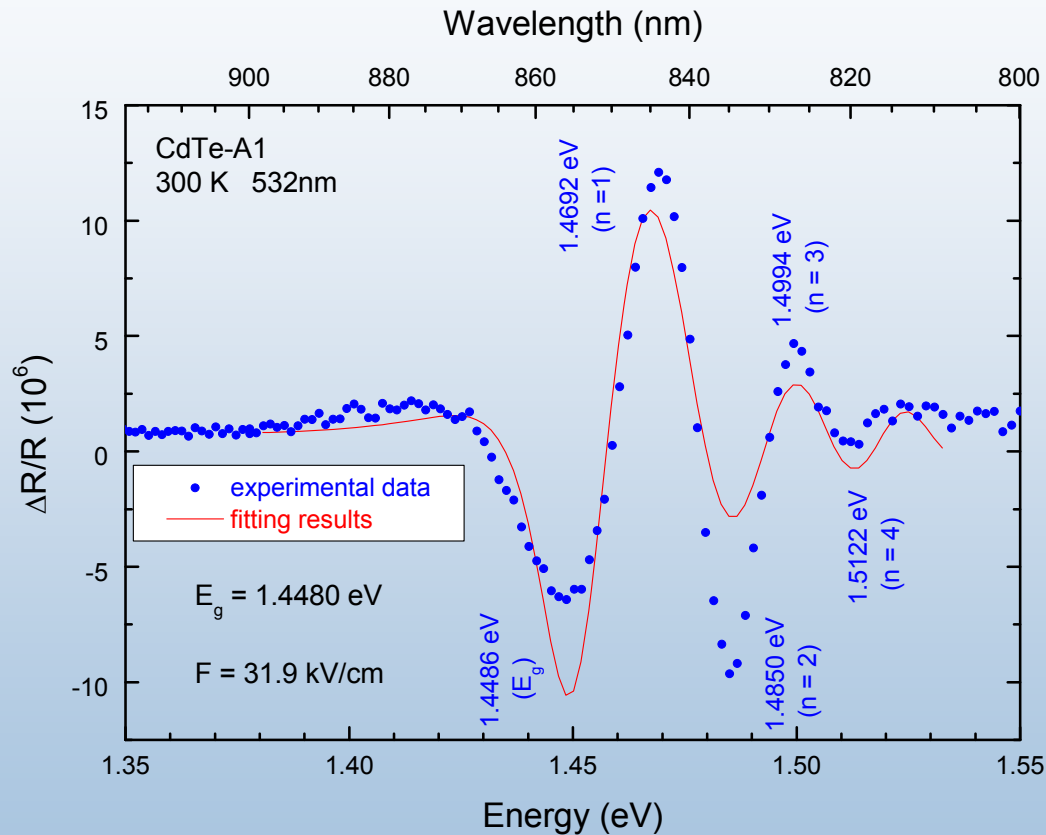
$$\Delta\varepsilon_1 = \frac{2e^2\hbar^2 |\vec{e} \cdot \vec{P}_{cv}|^2}{m^2 (\hbar\omega)^2} \left(\frac{2\mu_0}{\hbar^2}\right)^{3/2} \sqrt{\hbar\Omega_0} \left(G\left(\frac{E_g - \hbar\omega}{\hbar\Omega_0}\right) - \sqrt{\frac{E_g - \hbar\omega}{\hbar\Omega_0}} F\left(\frac{E_g - \hbar\omega}{\hbar\Omega_0}\right) \right)$$

$$F(\eta) = \pi[A_i'^2(\eta) - \eta A_i^2(\eta)]$$

$$G(\eta) = \pi[A_i'(\eta)B_i'(\eta) - \eta A_i(\eta)B_i(\eta)]$$

Shen & Pollak, Phys. Rev. B 42, 7097 (1990)

Photo-reflectance

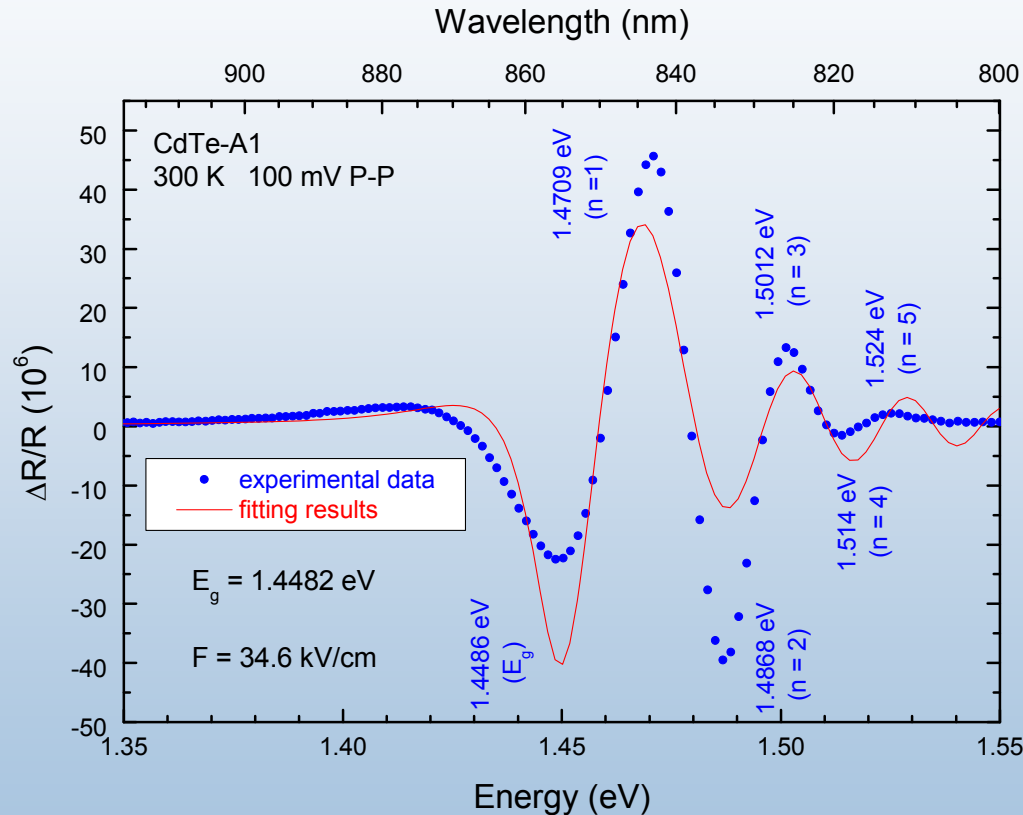


From Data fitting :

$$E_{\max} = 31.9 \text{ kV/cm}$$

$$E_g = 1.448 \text{ eV}$$

Electro-reflectance

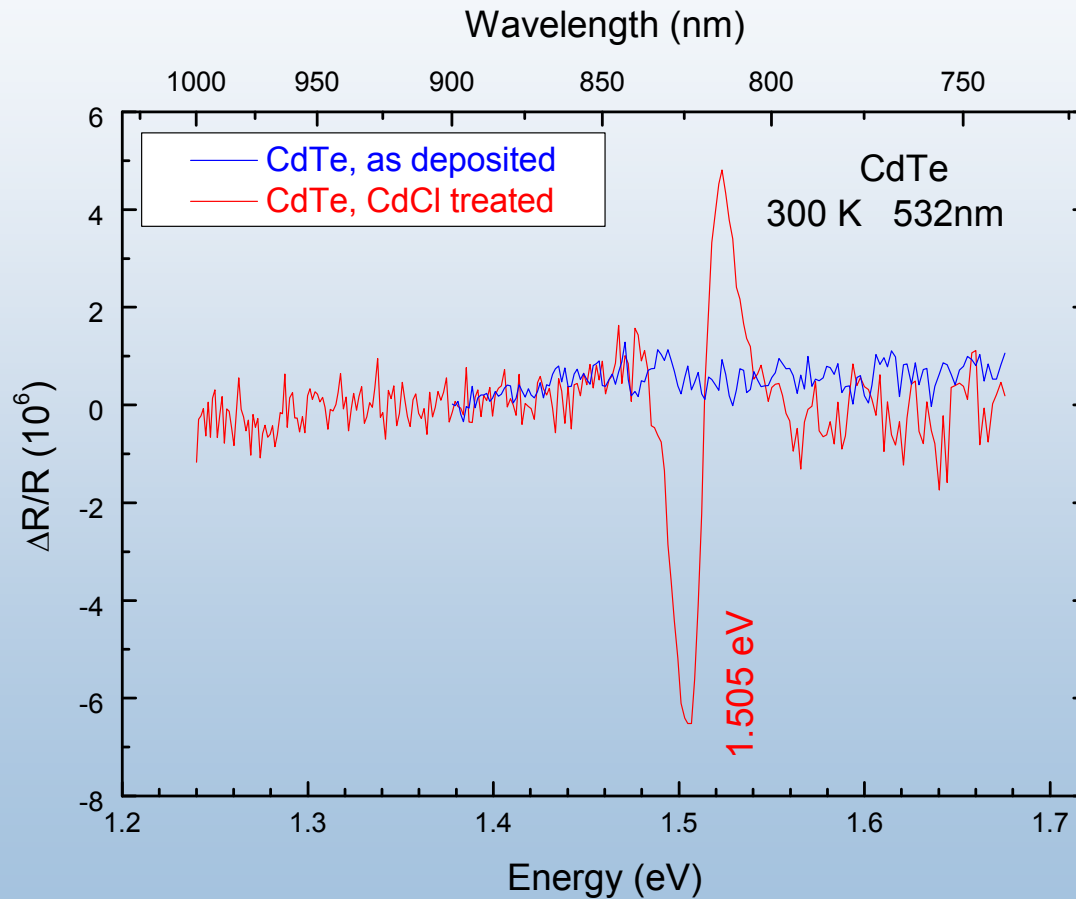


From Data fitting :

$$E_{\max} = 34.6 \text{ kV/cm}$$

$$E_g = 1.4482 \text{ eV}$$

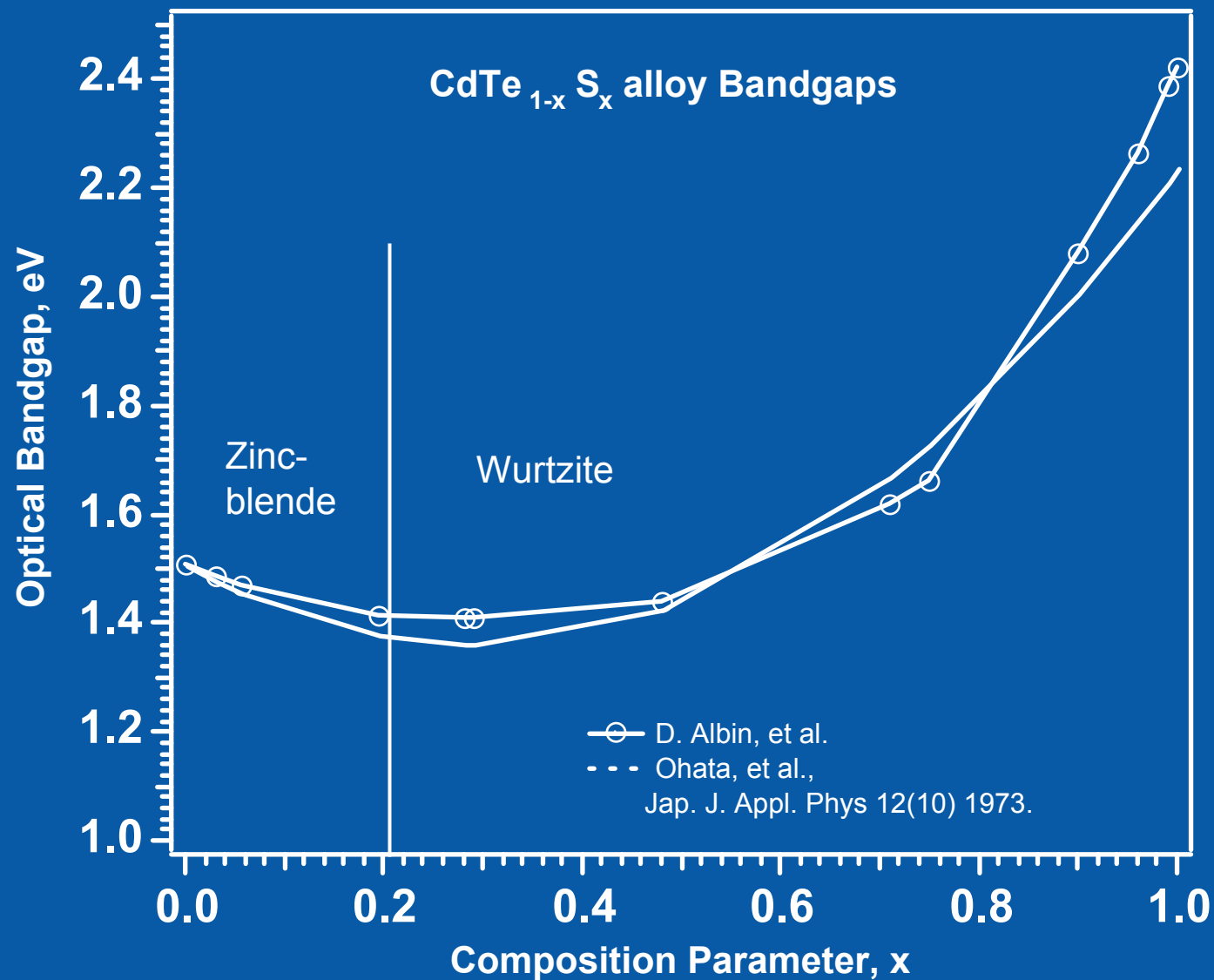
Effect of CdCl₂ treatment (by PR)



Modulated Reflectance

- **Modulated electro-reflectance and photo-reflectance studies identify a region of high electric field ($\sim 32\text{-}35$ kV/cm) for high efficiency CdS/CdTe devices. The field is present in the region of 1.45 eV material.**
- **SnO₂/CdTe devices do not show high field region**

The high field region corresponds to Te-rich CdSTe alloy.



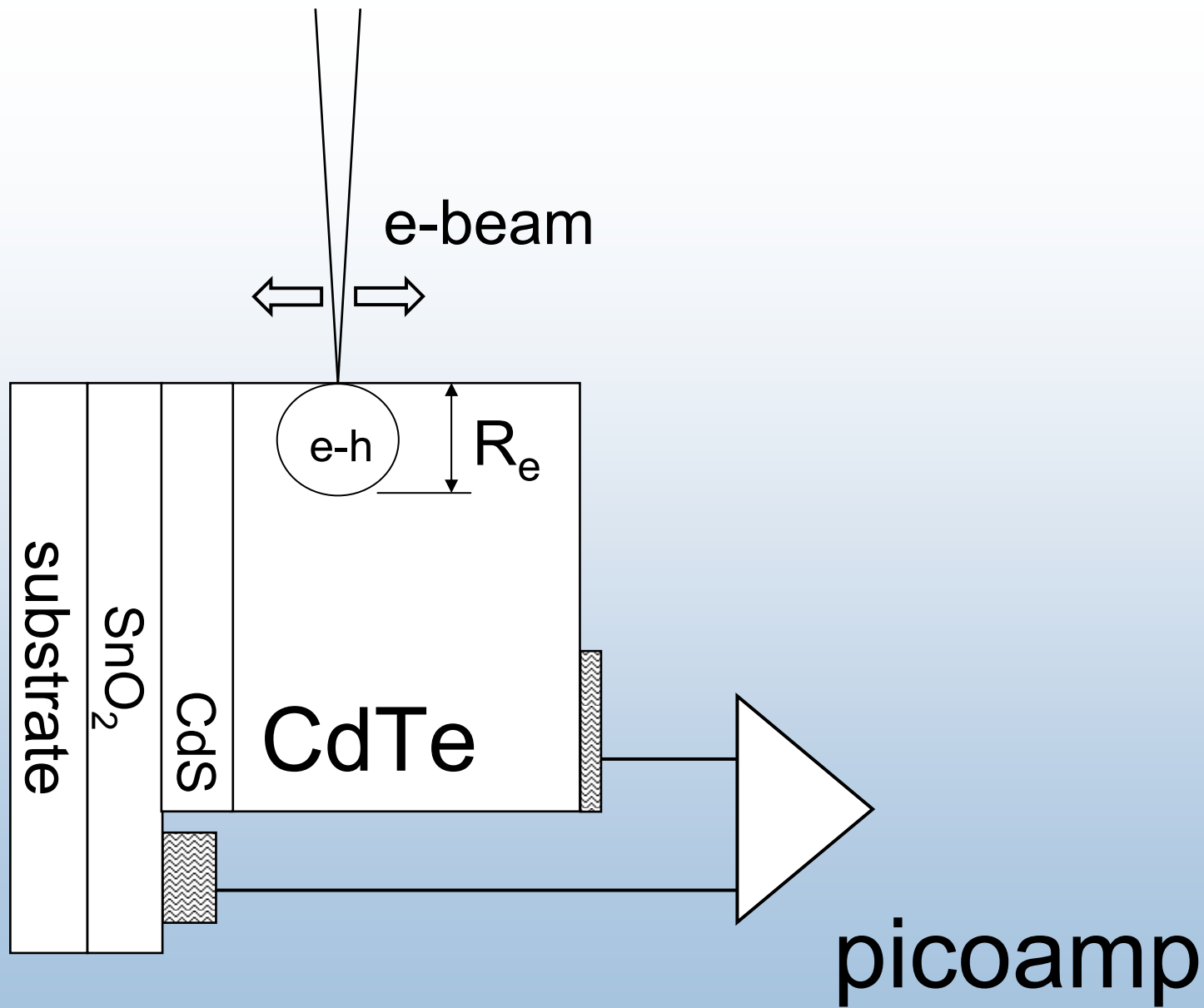
From $E_{\max} = 32 \text{ kV}$ and
depletion width on p-side = $3 \text{ } \mu\text{m}$ (base on
C-V and EBIC results)

Using $E_{\max} = qN_A X_p / \epsilon_s$
Gives $N_A = 5.5 \times 10^{14} \text{ cm}^{-3}$

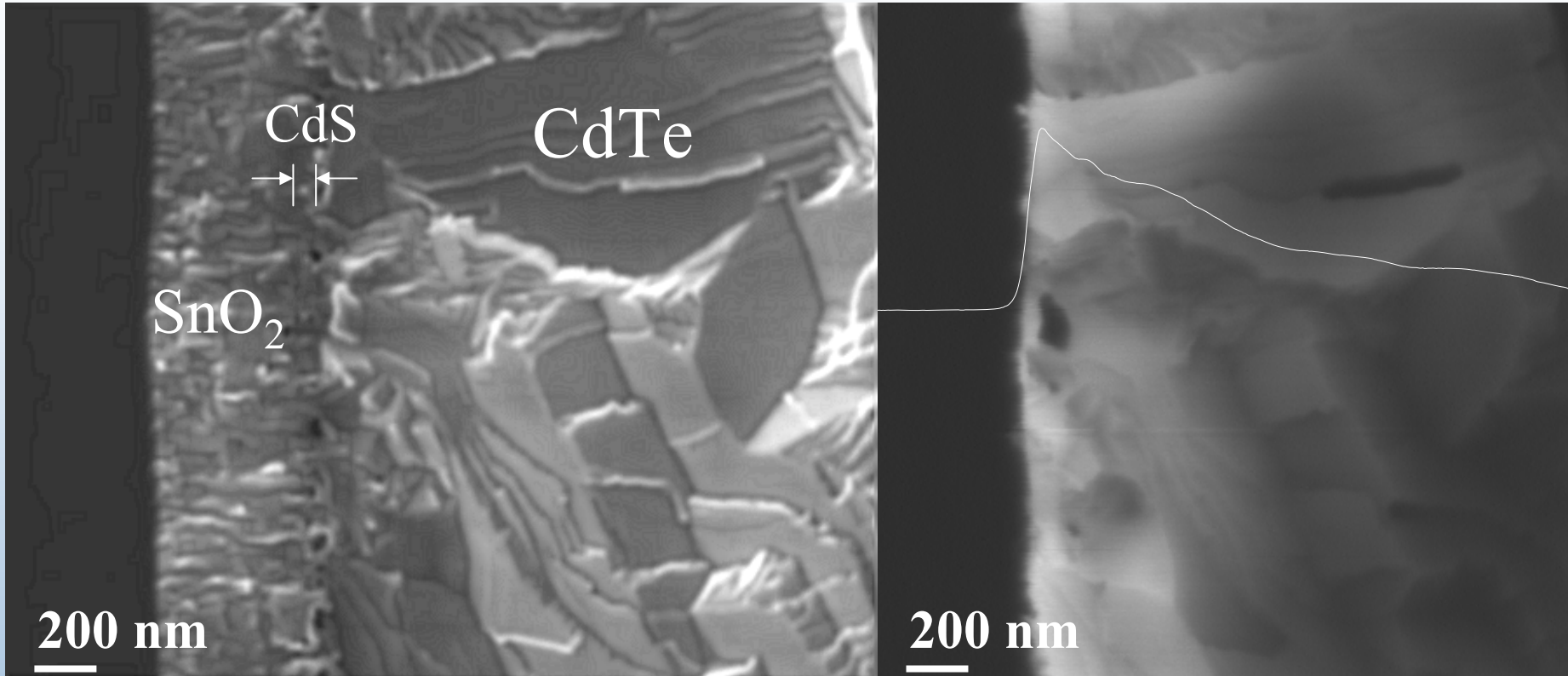
Evaluation of N_D based on SIMS and
EBIC results

EBIC

- SEM and HR-EBIC measurements performed on high V_{oc} (835 mV) device.
- Measurements on the cross-section of the device. Shows EBIC response close to CdS/CdTe interface.

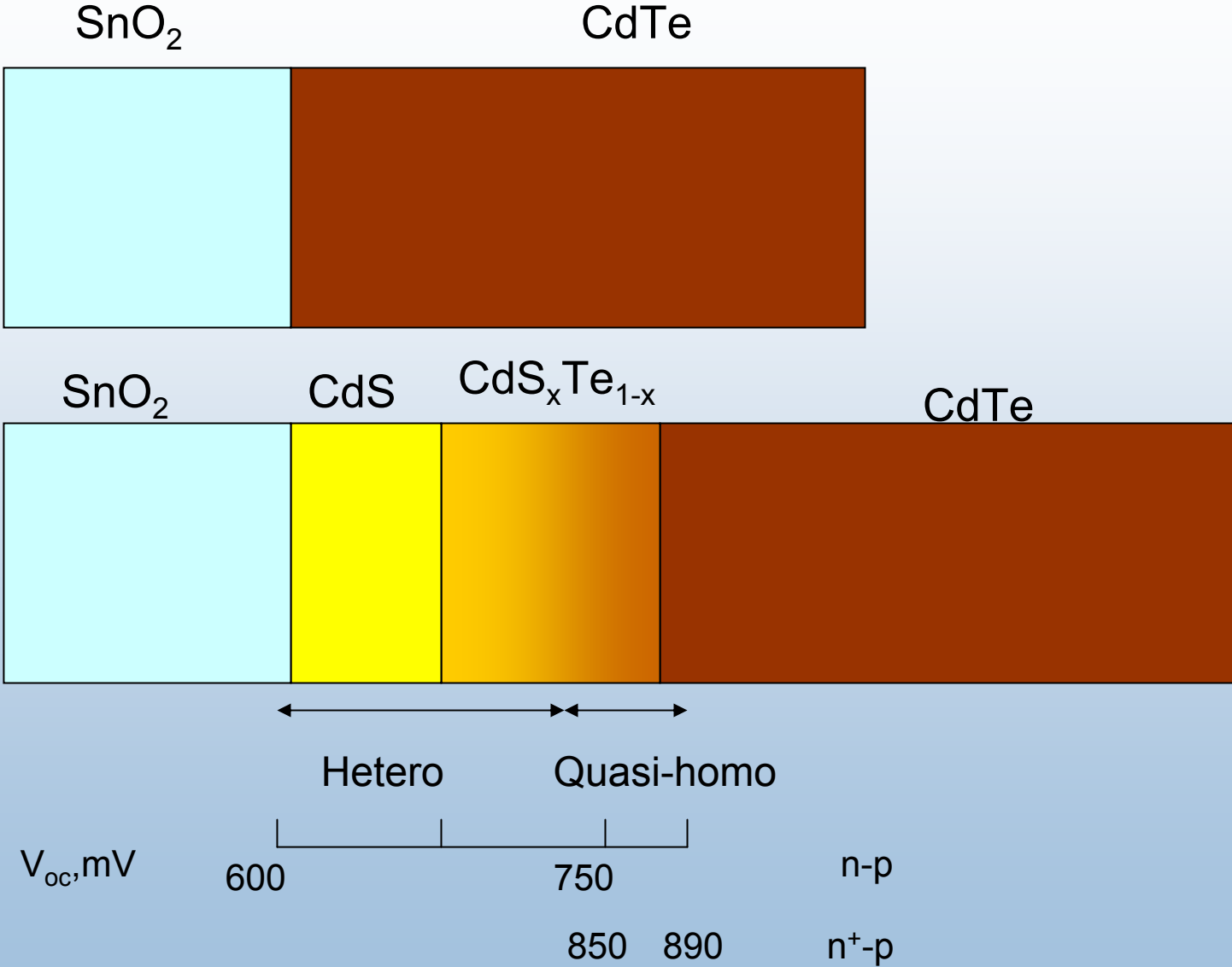


Electron-beam-induced-current



HREBIC

Device model



Device structure	V_{oc} , mV
SnO ₂ /CdTe	600-650
CdS/CdTe as dep	720-750
CdS/CdTe w/ CdCl ₂	840-850

- Lower V_{oc} devices are true hetero-junctions, whereas the devices with CdCl₂ treatment have a junction between n⁺ Te-rich CdS_{Te} alloy (doped with Cl) and p-type CdTe with compatible cubic structure i.e. quasi-homojunction.
- A true hetero-junction CdS/CdTe device performance will be dominated by interface defects at the hetero-interface which will be within the depletion region. This may be the case for as deposited devices fabricated at lower temperatures and SnO₂/CdTe devices giving low V_{oc} .
- Role of CdS is mainly to produce Te rich alloy layer that gets doped to n-type during CdCl₂ process and passivation of the surface.